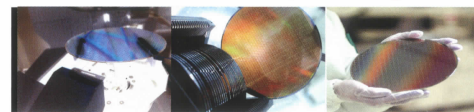


The Development and the commercialization of the Mask Aligner for wafer
Midas System will continue to grow along with the value creation for our customers.

<http://www.aligner.co.kr>

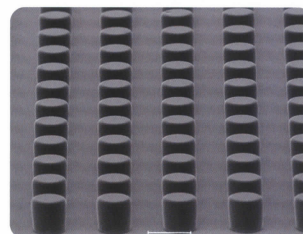
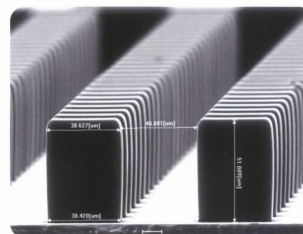
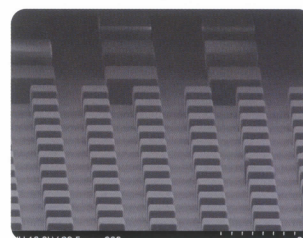
MDA-12SA



The MDA-12SA is brand new model and represents next generation of Full-field lithography systems. This brand new Semi-auto Aligner platform offers a higher Overlay Accuracy and more reliable operation. It is good for Ceramic, other Probe Card and WLP applications, This machine has higher productivity and easy to control.



▼ SEM Image



ITEM	SPECIFICATIONS
Substrate Size	Up to 12 inch
UV Lamp Power	2 kW
Resolution	down to 3 μ m (*FT=1 μ m @ 12 inch Si Wafer)
Alignment Accuracy	$\pm 3\mu$ m
Lamp Uniformity	$\leq \pm 5\%$
Uniform Beam Size	14.25" \times 14.25"
365nm Beam Intensity	15~20mW/cm ² (Broad band)
Exposure Time	0.1 ~ 999.9 sec
Motorized	Microscope X, Y -axis, Zoom and Focus Stage X, Y, θ and Z-axis
Process mode	Vacuum, Hard, Soft and Proximity
Dimension	1,700 \times 1,500 \times 2,100 mm



589,Yongsan-dong, Yuseong-gu, Daejeon, 305-500, Korea
Tel : +82-42-936-7620 / Fax : +82-42-936-7623 / A/S Center : +82-1544-7618
Homepage : www.aligner.co.kr / www.midas-system.com / E-mail : peter@aligner.co.kr